

Title (en)

Apparatus and method for anodic treatment.

Title (de)

Vorrichtung und Verfahren zur anodischen Behandlung.

Title (fr)

Appareil et procédé pour traitement anodique.

Publication

**EP 0202870 A1 19861126 (EN)**

Application

**EP 86303710 A 19860515**

Priority

US 73536785 A 19850517

Abstract (en)

A method for anodic surface treatment of metal surfaces comprising the steps of providing a treatment container containing a treatment solution comprising one or more of the following substances: tap water, dilute nitrate salts, dilute hydrochloric acid, dilute nitrite salts, dilute sulfuric acid, stannous and stannic salts and dilute nitric acid, positioning at least first and second electrodes in the treatment container, applying AC electrical current across the electrodes and causing a metal element to be located in the treatment container during application of the AC electrical current across the electrodes. DC surface treatment is also described.

IPC 1-7

**C25F 1/06**; **C25F 7/00**; **C25D 11/02**; **C25D 7/06**

IPC 8 full level

**C25F 7/00** (2006.01); **C25D 5/00** (2006.01); **C25D 7/06** (2006.01); **C25D 11/02** (2006.01); **C25D 11/04** (2006.01); **C25D 11/06** (2006.01); **C25D 11/08** (2006.01); **C25F 1/00** (2006.01); **C25F 3/02** (2006.01)

CPC (source: EP)

**C25D 7/0614** (2013.01); **C25D 11/005** (2013.01); **C25D 11/02** (2013.01); **C25F 1/00** (2013.01)

Citation (search report)

- US 4448475 A 19840515 - REZNICK DAVID [IL]
- DE 2646697 A1 19770428 - NAT STEEL CORP
- DE 1496808 A1 19700910 - GEN DYNAMICS CORP
- PATENT ABSTRACTS OF JAPAN, unexamined applications, C field, vol. 8, no. 193, September 5, 1984 THE PATENT OFFICE JAPANESE GOVERNMENT page 94 C 241 \* JP-A 59 85 893 (SHIN NIPPON SEITETSU K.K.) \*

Cited by

WO2012097927A1; US5449447A; CN103429795A; WO2010055145A1; WO9206231A3; DE102011002836A1; WO2012097926A1; US9909227B2; DE102011002837A1; US10011915B2

Designated contracting state (EPC)

AT BE CH DE FR GB IT LI LU NL SE

DOCDB simple family (publication)

**EP 0202870 A1 19861126**; AU 5751686 A 19861120; JP S6217198 A 19870126; ZA 863692 B 19870325

DOCDB simple family (application)

**EP 86303710 A 19860515**; AU 5751686 A 19860516; JP 11183786 A 19860517; ZA 863692 A 19860519